PMMA Resist – Processing Information

Introduction
PMMA (poly(methyl-methacrylate)) is a widely used, versatile, positive tone electron beam resist that is used for many micro-electronic applications. EM Resist can supply PMMA in Anisole at various dilutions for your applications.

Typical Processing Conditions
The processes outlined below are our standard processes. Other common resist processes can also be used.

Substrate Preparation:
Solvent clean with Acetone and IPA.

Spin Coating:
See spin curves below.

Baking:
Hot plate @ 180ºC for 120–180 seconds.

Exposure:

<table>
<thead>
<tr>
<th>Exposure @ 30 kV</th>
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<tbody>
<tr>
<td>Tungsten</td>
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<tr>
<td>SPL clearing dose</td>
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<tr>
<td>Area clearing dose</td>
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Development:
MIBK:IPA (1:3) for 30 seconds, followed by a rinse in IPA for 15 seconds.

Hard-Bake:
Convection oven @ 80ºC for 30 minutes.

Stripper:
Acetone

For more information or to enquire about using our equipment, please call or email us.

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